

<b>FORM PTO-1449</b>		Atty. Docket No.: I69.12-0556	Application No.: <u>10/674,173</u>
<b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b>		First Named Inventor: Kalman Pelhos et al.	
		Filing Date: Herewith	Group Art: <u>1713</u>

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate
HCL	AA 4,395,439	07/26/83	Kitamoto et al.	427	132	05/19/81
HCL	AB 4,426,265	01/17/84	Brunsch et al.	204	192 M	02/26/82
HCL	AC 4,950,548	08/21/90	Furusawa et al.	428	611	05/23/89

**FOREIGN PATENT DOCUMENTS**

	Document No.	Date	Country	Class	Sub Class	Translation Yes No

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

HCL	AD	Eiji Kita, Kimiteru Tagawa, Masafumi Kamikubota and Akira Tasaki; Magnetic recording media prepared by oblique incidence; November 1981; IEEE Transactions on Magnetics, Vol. Mag-17, No. 6
HCL	AE	R. Sugita, N. Echigo, K. Tohma and C. Yamamitsu; Incident angle dependence of recording characteristics of vacuum deposited Co-Cr Films; September 1990; IEEE Transactions on Magnetics, Vol. 26, No. 5
HCL	AF	J.P.C. Bernards, G.J.P. van Engelen, C.P.G. Schrauwen, H.A.J. Cramer, S.B. Luitjens; Simulation of the recording process with a VSM on Co-Cr and Co-Ni-O layers deposited at oblique incidence; September 1990; IEEE Transactions on Magnetics, Vol. 26, No. 5
HCL	AG	Ki-Seok Moon and Sung-Chul Shin; Dependence of structural and magnetic properties on deposition angle in electron-beam evaporated Co/Pt multilayer thin films; 1996; American Institute of Physics
HCL	AH	Yung-Chieh Hsieh and Sergei Gadetsky; Takao Suzuki; M. Mansuripur; Oblique sputtering of amorphous TbFeCo thin films on glass substrates and the effect of deposition angle on perpendicular magnetic anisotropy; 1997; American Institute of Physics
HCL	AI	R. D. McMichael; C. G. Lee; J. E. Bonevich, P. J. Chen, W. Miller, and W. F. Egelhoff, Jr.; Strong anisotropy in thin magnetic films deposited on obliquely sputtered Ta underlayers; November 1, 2000; Journal of Applied Physics Volume 88, Number 9
HCL	AJ	M.J. Hadley, R. Atkinson, R.J. Pollard; Magnetic properties of Co films deposited onto obliquely sputtered Ta underlayers; 2002; Elsevier Science B.V.

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10/674,173

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## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HCL	AK	M. Cartier, S. Auffret, P. Bayle-Guillement, F. Ernult, F. Fettar, and B. Dieny; Influence of deposition angle on the properties of NiO spin-valves; February 1, 2002; American Institute of Physics
HCL	AL	U. F. Zheng and J. P. Wang; Control of the tilted orientation of CoCrPt/Ti thin film media by collimated sputtering; May 15, 2002; American Institute of Physics
HCL	AM	A. Lisfi, J. C. Lodder, H. Wormeester, and B. Poelsema; Reorientation of magnetic anisotropy in obliquely sputtered metallic thin films; 2002; The American Physical Society Physical Review B 66, 174420 (2002)
HCL	AN	Anup G. Roy and David E. Laughlin; Effect of seed layers in improving the crystallographic texture of CoCrPt perpendicular recording media; May 15, 2002; Journal of Applied Physics; Volume 91, Number 10

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*H. Liles*

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LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	First Named Inventor: Kalman Pelhos	
	Filing Date: September 29, 2003	Group Art: 2652 1773

## U.S. PATENT DOCUMENTS

Examiner Initials	Document No.	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents
AA			
AB			

## FOREIGN PATENT DOCUMENTS

		Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents	Translation Yes No
HCL	AC	WO8007250	06-14-1994	Hitachi Ltd	No
HCL	AD	2002042326	07-19-00	KYOCERA CORP	Yes

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HCL	AE	Kiwamu Tanahashi, Yuzuru Hosoe, Masaaki Futamoto; <i>Magnetic Anisotropy and Microstructure of Obliquely Evaporated Co/Cr Thin Films</i> ; July 24, 1995; pgs. 265 - 272.
HCL	AF	Y.F. Zheng and J.P. Wang; <i>Control of the Tilted Orientation of CoCrPt/Ti thin film media by collimated sputtering</i> ; May 15, 2002; V931 pgs. 0007 - 0009.
HCL	AG	M.J. Hadley, R. Atkinson, R.J. Pollard; <i>Magnetic Properties of Co Films Deposited Onto Obliquely Sputtered Ta Underlayers</i> ; January 31, 2002.
HCL	AH	Dieter Weller and Andreas Moser; <i>Thermal Effect Limits in Ultrahigh-Density Magnetic Recording</i> ; November 1999; volume 35, pgs. 4423 - 4439.
HCL	AI	R.D. McMichael, C.G. Lee, J.E. Bonevich, P.J. Chen, W. Miller, and W.F. Egelhoff, Jr; <i>Strong Anisotropy in Thin Magnetic Films Deposited on Obliquely Sputtered Ta Underlayers</i> ; volume 88, No. 9, pgs. 5296 - 5299.0
HCL	AJ	A. Hagemeyer, H.J. Richter, H. Hibst, V. Maier and L. Marosi; <i��格组织和形态学的倾斜沉积co-cr磁性薄膜在柔性聚合物基底上< i="">; August, 10, 1993; pgs. 199 - 202.</i��格组织和形态学的倾斜沉积co-cr磁性薄膜在柔性聚合物基底上<>
HCL	AK	T. Hikosaka, Y. Tamaka, T. Sonoda, and R. Nishikawa; <i>Cr Underlayer's Effect on the Magnetic and Crystalline Properties of Co Alloy Film</i> ; June 1988; volume 3, No. 6, pgs. 423 - 424.
HCL	AL	J.C. Lodder; <i>Magnetic Thin Films for High-Density Recording</i> ; 1996; pgs 474 - 483

EXAMINER: H. Weller DATE CONSIDERED: 10/24/09

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